



Patent Application No. 10/791,014  
Customer Number: 42717

IRW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Chung-Shi Liu, et al.	§	Docket No.:	24061.596
		§		(TSMC2000-0488)
Serial No.:	10/791,014	§		
		§	Examiner:	Fetsum Abraham
Filing Date:	March 2, 2004	§		
		§	Art Unit:	2826
For:	Prevention of Post CMP Defects	§		
	in CU/FSG Process	§	Conf. No.:	1306
		§		

**RESPONSE TO RESTRICTION REQUIREMENT**

Mail Stop: Amendment  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed March 22, 2005, applicant hereby elects, Group II, Claims 35-44, which is drawn to a method of making a semiconductor device.

Applicant's election is made with traverse on the grounds that the embodiments delineated by the examiner are not patentably distinct and therefore constitute a single invention concept.

An early action on the merits is respectfully requested.

Respectfully submitted,

Wei Wei Jeang  
Reg. No. 33,305

Date:

April 11, 2005

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**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Mail Stop: Amendment, Commissioner For Patents, PO Box 1450, Alexandria, VA 22313-1450 on the date below.

Kelly A. Moreau

Name

April 11, 2005

Date